

REMARKS

The above amendments are presented in order to place the application into a format consistent with U.S. practice. A markup sheet is provided at the end of this document to illustrate the changes made for the Examiner.

Respectfully submitted,


James H. Walters, Reg. No. 35,731

802
DELLETT AND WALTERS
Suite 1101
310 S.W. Fourth Avenue
Portland, Oregon 97204 US
(503) 224-0115
DOCKET: A-413

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and a process in which repeating pattern data of grating-shaped grooves and strips, which have different pitches, are written in juxtaposition with each other.

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Brief Description of the Drawings

Fig. 1 is a diagram for describing the principle that the connection error at the joint between patterns is minimized by the present invention.

Figs. 2(a) and 2(b) comprise diagrams

10 ~~Fig. 2 is a diagram~~ showing an electron beam writing method used in the method of producing a phase mask, and also showing a section of the phase mask.

Fig. 3 is a diagram showing the way in which a pattern having a varying pitch is written by connecting together patterns having different pitches.

Figs. 4(a) through 4(h) are views

15 ~~Fig. 4 is a sectional view~~ showing steps of an embodiment of the phase mask producing method according to the present invention.

Figs. 5(a) through 5(c) comprise diagrams

~~Fig. 5 is a diagram~~ for describing optical fiber processing and a phase mask used therefor.

20 Fig. 6 is a diagram schematically showing the way in which a phase mask pattern is written with an electron beam by using an electron beam writing system.

Fig. 7 is a diagram showing the way in which a plurality of patterns having different pitches are written
25 by multiple writing operations carried out in opposite directions.

Fig. 8 is a diagram showing the way in which a plurality of patterns having different pitches are written

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